10/591718 AP20 Rec'd PCT/PTO 05 SEP 2006 PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s):

Ishiduka et al.

Examiner:

Unassigned

Application No.:

Unassigned

Group Art Unit:

Unassigned

Confirmation No:

Unassigned

Docket:

1608-7 PCT/US

Filed:

Herewith

Dated:

September 5, 2006

For:

POSITIVE-TYPE RESIST

COMPOSITION FOR LIQUID IMMERSION LITHOGRAPHY AND METHOD FOR FORMING

RESIST PATTERN

Commissioner for Patents P.O. Box 1450 Alexandria, Virginia 22313-1450

Dated: September 5, 2006 Label No. EV 881318080US I hereby certify that on the date indicated above I deposited this paper or fee with the U.S. Postal Service and that it was addressed for delivery to the

Commissioner of Patents, P.O. Box 1450, Alexandria, VA 22313-1450 by EXPRESS MAIL POST OFFICE to ADDRESSEE service.

Barbara Thomas Name (Print)

(Signature)

INFORMATION DISCLOSURE STATEMENT

Sir:

In order to fulfill the requirements of candor and good faith set forth in 37 C.F.R. §1.56, Applicants submit herewith the following Information Disclosure Statement in accordance with the provisions of 37 C.F.R. §1.97 and §1.98. It is understood that the information provided herein is solely for the purpose of fulfilling Applicants' obligations under the law and should not be construed as nor is it intended to be an admission of prior art.

Pursuant to the PTO's waiver under 37 C.F.R. §1.98(a)(2)(ii), no copies of the granted U.S. patent and/or the published U.S. patent application references listed on the

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attached Form PTO-1449 are being submitted herewith.

This Statement is also being filed concurrently with the application and is timely pursuant to 37 C.F.R. §1.97.

The Commissioner is hereby authorized to charge payment of any additional fees associated with this communication, or credit any overpayment, to Deposit Account No. 08-2461. Such authorization includes authorization to charge fees for extensions of time, if any, under 37 C.F.R § 1.17 and also should be treated as a constructive petition for an extension of time in this reply or any future reply pursuant to 37 C.F.R. § 1.136.

If the Examiner has any questions or comments relating to the present application, he or she is respectfully invited to contact Applicants' attorney at the telephone number set forth below.

Respectfully submitted,

Jamie M. Larmann

Registration No.: 48,623 Attorney for Applicants

HOFFMANN & BARON, LLP 6900 Jericho Turnpike Syosset, New York 11791 (973) 331-1700

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ATTY. DOCKET NO. FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE 1608-7 PCT/US Unassigned (Rev. 2-32) CONFIRMATION NO. INFORMATION DISCLOSURE APPLICANT STATEMENT BY APPLICANT Ishiduka et al. Unassigned **GROUP** FILING DATE (Use several sheets if necessary) Unassigned Herewith U.S. PATENT PUBLICATIONS **EXAMINER DOCUMENT** SUB CLASS DATE NAME FILING DATE INITIAL NUMBER CLASS IF APPROPRIATE 2003/ 0078352 04/24/03 Miyazawa et al. 2003/ 0224283 12/04/03 Allen et al. U.S. PATENT DOCUMENTS DOCUMENT **SUB EXAMINER** CLASS FILING DATE NAME DATE CLASS INITIAL **NUMBER** IF APPROPRIATE FOREIGN PATENT DOCUMENTS **TRANSLATION EXAMINER** DOCUMENT SUB COUNTRY CLASS DATE CLASS INITIAL NUMBER YES NO WO 2004/ **PCT** 088429 10/14/04 WO 99/ **PCT** 49504 09/30/99 12/28/05 **EPO** EP 1610178 JP 2005-055890 03/03/05 Japan (abstract) JP 2004-02/12/04 Japan (abstract) 046098 JP 2004-Japan (abstract) 03/04/04 069981 JP 2003-040840 02/13/03 Japan (abstract) JP 2002-06/14/02 Japan (abstract) 169287 **DATE CONSIDERED EXAMINER**

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